

**10/565104**

**IAP20 Rec'd PCT/PTO 19 JAN 2006**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :  
Hiroki MAEDA et al. : **Mail Stop: PCT**  
Serial No. NEW : Attorney Docket No. 2006\_0043A  
Filed January 19, 2006 :

PHOTOSENSITIVE RESIN  
COMPOSITION AND METHOD OF  
FORMING A PATTERN USING  
THE COMPOSITION  
[Corresponding to PCT/JP2004/018759  
Filed December 15, 2004]

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**PRELIMINARY AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In the interest of compact prosecution, please amend the present application as follows:

ATTACHMENT F


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3. ☐ Consideration of the following list of additional information (including any copending or abandoned U.S. application, prior uses and/or sales, etc.) is requested.
4. For each non-English language reference listed on the attached form PTO-1449, reference is made to:
- a. ☐ a full or partial English language translation submitted herewith,
  - b. ☒ a foreign patent office (International) search report (in the English language) submitted herewith (Attachment G),
  - c. ☒ the concise explanation contained in the specification of the present application at pages 2 and 3,
  - d. ☒ the concise explanation set forth in the attached English language abstract,
  - e. ☒ the concise explanation set forth below or on a separate sheet attached to the reference:
- JP 7-78628 B2 corresponds to U.S. 4,882,245  
-JP 2-279718 corresponds to U.S. 5,026,624  
-EP 0 927 726 A1 corresponds to JP 10-147608
5. ☐ A foreign patent office search report citing one or more of the references is enclosed.

Respectfully submitted,

THE COMMISSIONER IS AUTHORIZED  
TO CHARGE ANY DEFICIENCY IN THE  
FEES FOR THIS PAPER TO DEPOSIT  
ACCOUNT NO. 23-0975

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